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Dae Wook Kim
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Contents

vii	<i>Authors</i>
ix	<i>Conference Committee</i>

SESSION 1	OPTICAL SYSTEMS I
9575 02	Examination of the quality of 120 degree silicon double mirror for a micro-optical laser gyroscope [9575-1]
9575 04	JWST pathfinder telescope integration [9575-3]
9575 05	JWST pathfinder telescope risk reduction cryo test program [9575-4]
SESSION 2	OPTICAL SYSTEMS II
9575 06	Optomechanical design and tolerance of a microscope objective at 121.6 nm [9575-5]
9575 08	Metrology requirements for the serial production of ELT primary mirror segments [9575-7]
SESSION 3	OPTICAL MANUFACTURING I
9575 09	Surface roughness when diamond turning RSA 905 optical aluminium [9575-10]
9575 0A	Aspects of ultra-high-precision diamond machining of RSA443 optical aluminium [9575-11]
9575 0B	The role of robotics in computer controlled polishing of large and small optics [9575-12]
9575 0C	Evaluation and control of spatial frequency errors in reflective telescopes [9575-13]
9575 0D	Correction of mid-spatial-frequency errors by smoothing in spin motion for CCOS [9575-57]
SESSION 4	OPTICAL MANUFACTURING II
9575 0H	Fabrication of freeform optics [9575-17]
9575 0J	Measuring skew in average surface roughness as a function of surface preparation [9575-49]

SESSION 5	OPTICAL MANUFACTURING III
9575 0L	Status of the Advanced Mirror Technology Development (AMTD) phase 2, 1.5m ULE® mirror [9575-21]
9575 0M	Improving profitability through slurry management: a look at the impact of slurry pH on various glass types [9575-22]
9575 0N	Material removal characteristics of orthogonal velocity polishing tool for efficient fabrication of CVD SiC mirror surfaces [9575-23]
9575 0O	Surface errors in the course of machining precision optics [9575-24]
9575 0P	The effect of deep HF etching on the surface quality and figure of fused silica optics [9575-59]
SESSION 6	OPTICAL MANUFACTURING IV
9575 0Q	Using frictional power to model LSST removal with conventional abrasives [9575-26]
9575 0R	Influence of coolant on ductile mode processing of binderless nanocrystalline tungsten carbide through ultraprecision diamond turning [9575-27]
9575 0S	Influence of temperature difference on surface figure controlling during continuous polishing [9575-60]
SESSION 7	OPTICAL TESTING I
9575 0W	Subaperture stitching surface errors due to noise [9575-32]
9575 0X	An iterative subaperture position correction algorithm [9575-33]
SESSION 8	OPTICAL TESTING II
9575 11	Measuring and quantifying scatter from non-isotropic sources [9575-36]
9575 12	Fabrication and qualification of roughness reference samples for industrial testing of surface roughness levels below 0.5 nm Sq [9575-37]
SESSION 9	OPTICAL TESTING III
9575 14	Oil defect detection of electrowetting display [9575-40]
9575 15	Deflectometry measurement of Daniel K. Inouye Solar Telescope primary mirror [9575-41]
9575 16	The use of diffractive imitator optics as calibration artefacts [9575-42]

POSTER SESSION

- 9575 19 **Investigation of rapidly solidified aluminum by using diamond turning and a magnetorheological finishing process** [9575-45]
- 9575 1A **Optical diffraction interpretation: an alternative to interferometers** [9575-46]
- 9575 1C **Noninvasive method for determination of parameters of cemented doublet** [9575-48]
- 9575 1D **Detection of subsurface defects and measurement of thickness of screen layers made of graphene and carbon nanotubes with application of full-field optical coherence tomography in Linnik configuration** [9575-50]
- 9575 1G **Designing null phase screens to test a fast plano-convex aspheric lens** [9575-53]
- 9575 1H **Null screens type Hartmann to test simple lenses** [9575-54]

Authors

Numbers in the index correspond to the last two digits of the six-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first four digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Abou-El-Hossein, Khaled, 09, 0A, 19	Hadaway, James B., 05
Allen, Richard G., 0Q	Hahn, Walter G., 04
Amon, John N., 04	Han, Jeong-Yeol, 0N
Asfour, Jean-Michel, 16	Havey, Keith A., Jr., 05
Atkinson, Charles B., 04	Hong, Meijuan, 0S
Audo, F., 1A	Hooper, Abigail R., 0M
Avendaño-Alejo, Maximino, 1G, 1H	Hsu, Wei-Yao, 09, 19
Bibby, Matt, 0B	Hu, Chen, 0D
Biskup, H., 0O, 12	Hu, Haixiang, 0C
Blalock, Todd, 0H	Huang, Run, 15
Boffa, Christopher C., 0M	Huang, Ting-Wei, 14
Bouillet, S., 1A	Hubler, William H., 0Q
Broccolo, Ronald T., 04	Huguet, Jesse A., 05
Burge, James H., 0W, 15	Johnson, Matthew, 0L
Castán-Ricaño, Diana, 1G, 1H	Jota, Thiago S., 06
Castillo-Santiago, Gabriel, 1H	Kennard, Scott H., 04
Chen, Yi-Chun, 0X	Keski-Kuha, Ritva, 04, 05
Cheng, Yuan-Chieh, 09, 19	Keyes, Derek S., 06
Chiang, Hou-Chi, 14	Kim, Gun-Hee, 06
Cumme, M., 12	Kim, Sug-Whan, 0N
Cureton, Kevin, 0M	Kim, Young-Sik, 06
Daly, Elizabeth A., 04	Klocke, Fritz, 0R
Dambon, Olaf, 0R	Kuo, Ching-Hsiang, 19
Daurios, J., 1A	Lander, Juli A., 05
DeGroote Nelson, Jessica, 0H	Langenbach, E., 12
DelOlmo-Márquez, Jesús, 1G	Leber, Ingmar, 02
Densmore, Víctor, 06	Lee, Haengbok, 0N
Díaz-Urbe, Rufino, 1G, 1H	Lee, Kyungmook, 0N
Dietzel, Andreas, 02	Levi, Joshua, 04
Doetz, Marius, 0R	Li, Hongyu, 0B
Dun, Aihuan, 0S	Lin, Po-Chih, 0X
Dunn, Christina, 0B	Liu, Shijie, 0D, 0P, 0S
Effinger, Michael R., 0L	Lo, Weng-Hou, 0X
Egerman, Robert, 0L	Lu, Chunlian, 0B
Ellis, James M., 04	Luepke, Dakota, 06
Eng, Ron, 0L	Lunt, Sharon, 05
Eupherte, L., 1A	Mang, Ou-Yang, 14
Fähnle, Oliver, 0R, 12	Marsh, James M., 05
Fechner, R., 12	Matthews, Gary W., 04, 05, 0L
Feinberg, Lee D., 04, 05	McKay, Andrew, 04
Ferland, Albert, 0L	Medicus, Kate, 0H
Fréville, S., 1A	Mikš, A., 1C
Frost, F., 12	Milster, Thomas D., 06
Gao, Weichuan, 06	Mitchell, John B., 16
Gao, Wenlan, 0P, 0S	Mkoko, Z., 09, 0A
González-Galindo, Alfredo, 1H	Mlynarska, Paulina, 1D
Gray, Caroline, 08	Mt. Pleasant, Stephen M., 04
Gu, Haojin, 0D	Nasyrov, Ruslan K., 16
Haberl, A., 0O	Niesel, Thalke, 02

Noël, Darin M., 05
 Novák, J., 1C
 Novák, P., 1C
 Otieno, Timothy, 09, 19
 Pakuła, Anna, 1D
 Pokorný, P., 1C
 Poleshchuk, Alexander G., 16
 Rascher, R., 0O, 12
 Rees, Paul C. T., 08, 16
 Rouyer, C., 1A
 Salbut, Leszek, 1D
 Sarkas, Harry W., 0M
 Schindler, A., 12
 Scorse, Thomas R., 05
 Seo, Hyunju, 0N
 Seong, Sehyun, 0N
 Shao, Jianda, 0D, 0P, 0S
 Sloma, Marcin, 1D
 Smith, Greg A., 0W
 Spina, John A., 05
 Stahl, H. Philip, 0L
 Stahl, Mark T., 0J
 Stover, John C., 11
 Su, Peng, 15
 Texter, Scott, 04
 Tomczewski, Sławomir, 1D
 Tsai, Yu-Hsiang, 14
 Volkov, Andy, 16
 Voyton, Mark F., 05
 Walker, Chanda B., 05
 Walker, David, 0B
 Wei, Chaoyang, 0D, 0P, 0S
 Weidner, Frank, 16
 Wells, Conrad, 05
 Whitman, Tony L., 05
 Wróblewski, Grzegorz, 1D
 Wu, Hsing Yu, 0B
 Wünsche, C., 12
 Xu, Jiafeng, 0P
 Xu, Xueke, 0D, 0P, 0S
 Yan, Yung-Jhe, 14
 Yang, Minghong, 0P, 0S
 Yoon, Siyoung, 0N
 Yu, Guoyu, 0B
 Zeng, Xuefeng, 0C
 Zhang, Haichao, 0D
 Zhang, Xuejun, 0C
 Zhang, Yang, 0S
 Zhang, Yizhong, 0D
 Zheng, Ligong, 0C
 Zheng, Xiao, 0B
 Zygal'sky, F., 12

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David D. Walker, Zeeko Research Ltd. (United Kingdom)
- 7 Optical Testing I
Ray Williamson, Ray Williamson Consulting (United States)
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